

# Compositional Effects on Thermal and Electrical Properties of Dielectric Glass Paste

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## Abstract

The effect of  $\text{Al}_2\text{O}_3$  on the dielectric constant and the coefficient of thermal expansion of lead borosilicate glasses for the application of PDP glass paste was investigated. Measurements were made theoretically by using empirical equations on the composition of the glasses in which the  $\text{PbO}/\text{Al}_2\text{O}_3$ ,  $\text{B}_2\text{O}_3/\text{Al}_2\text{O}_3$  and  $\text{SiO}_2/\text{Al}_2\text{O}_3$  ratios were systematically varied. As a result, with increasing  $\text{PbO}/\text{Al}_2\text{O}_3$  the thermal expansion coefficient and the dielectric constant noticeably increased, while the change of  $\text{B}_2\text{O}_3/\text{Al}_2\text{O}_3$  and  $\text{SiO}_2/\text{Al}_2\text{O}_3$  ratios did not affect those properties of the glasses.

## Introduction

Flat display panel is becoming a major new application for high-performance glass because this device offers advantage over CRT in terms of less weight and smaller size. The  $\text{PbO-SiO}_2\text{-Al}_2\text{O}_3\text{-RO}$  ( $\text{R}_2\text{O}_3$ ) glasses have been the most commonly used system for frit glass and glass paste in plasma display panel (PDP) industry [1,2]. The main different composition of glass paste for double layers (upper and lower) is generally the existence of  $\text{Al}_2\text{O}_3$ : upper layer does not contain  $\text{Al}_2\text{O}_3$ , but lower one does. In the glass paste,  $\text{Al}_2\text{O}_3$  can affect the electrical and the thermal properties of dielectric and act as an intimidator for the substrate glass, which is a soda-lime-silica glass with a softening temperature of  $723^\circ\text{C}$  [3]. The reasonable dielectric for PDP should have the same thermal expansion coefficient with the substrate and high dielectric constant as well as high thermal conductivity. For the development of an ideal dielectric for PDP, it would require several properties: to prevent formation of air bubbles, to make transparency above 80% after firing, to increase voltage with a thin film, and to match very well with bus electrode. To develop a new dielectric glass paste for low temperature firing, however, design of glass composition is the most important stage for the purpose.

In this work, we limited the measurements, dielectric constant and thermal expansion coefficient in the various properties. The optimum conditions, in producing dielectric layer for PDP, which have high dielectric constant and low thermal expansion coefficient are theoretically investigated only as a function of compositions, especially different oxide ratios  $\text{PbO}/\text{Al}_2\text{O}_3$ ,  $\text{B}_2\text{O}_3/\text{Al}_2\text{O}_3$  and  $\text{SiO}_2/\text{Al}_2\text{O}_3$ .

## Theoretical background

It can be easily obtained on the optimum conditions of electrical and thermal properties based on a mixture rule that each property is closely related with their composition [4].

### • Dielectric constant

$$\epsilon = 10^{-2} \sum \epsilon_i (\text{mol}\%)_i \quad (1)$$

### • Coefficient of thermal expansion

$$\alpha = \sum \alpha_i (\text{wt}\%)_i \quad (2)$$

where  $\epsilon_i$  and  $\alpha_i$  are the additivity factors or the property coefficients for a given component  $i$ . The compositions considered in this work were varied in the following range:  $\text{PbO}$  (60-70wt%),  $\text{B}_2\text{O}_3$  (10-25wt%),  $\text{SiO}_2$  (5-20wt%) and  $\text{Al}_2\text{O}_3$  (5-25wt%). Compositions of  $\text{PbO-B}_2\text{O}_3\text{-SiO}_2\text{-Al}_2\text{O}_3$  glasses with variable ratios

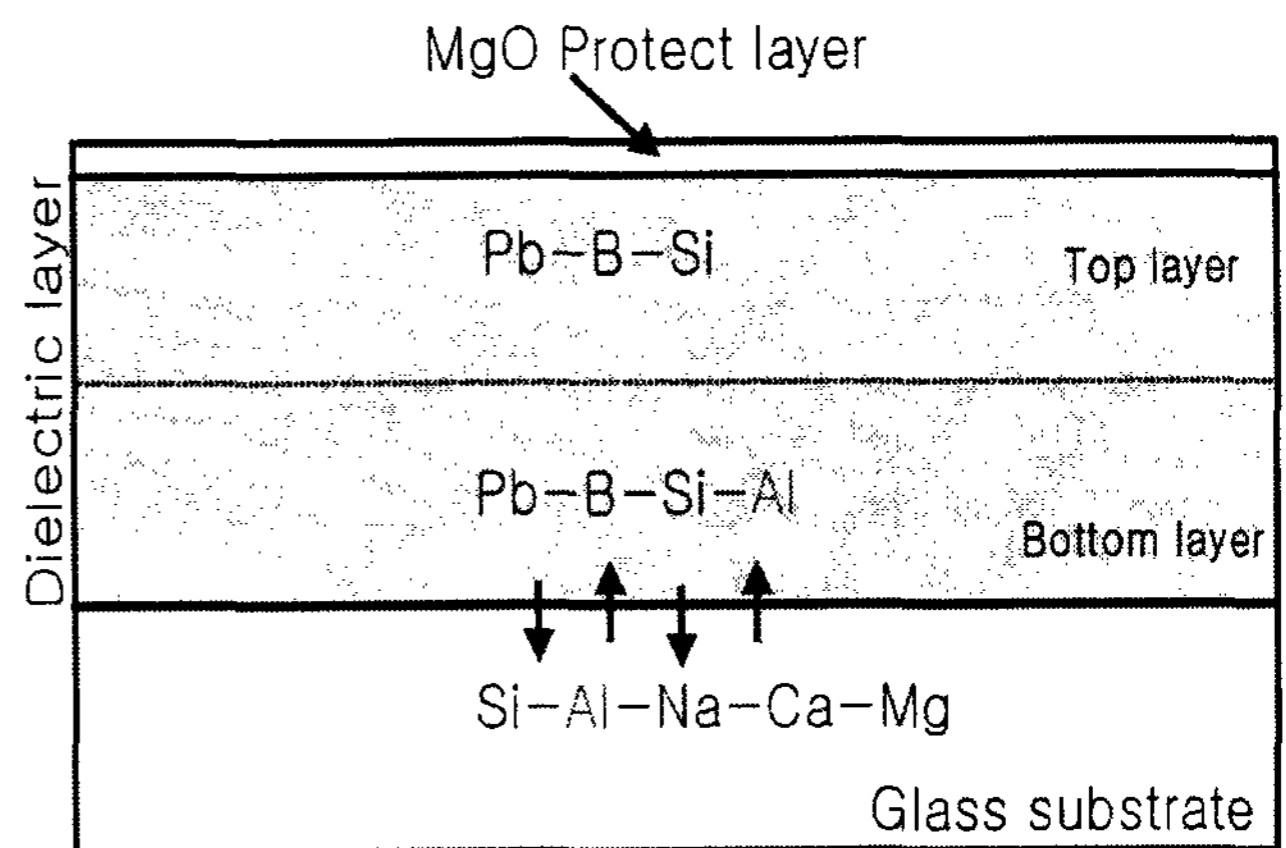


Fig. 1. The schematic of cross section of dielectric layer and substrate in PDP

are in Table 1.

Figure 1 shows the cross section of dielectric and substrate in PDP. The behavior of  $\text{Al}_2\text{O}_3$  is important in dielectric layer in terms of viscosity of glass and ion diffusion during firing stage.  $\text{Al}_2\text{O}_3$  contained in dielectric layer and substrate can easily move to each layer. Therefore  $\text{Al}_2\text{O}_3$  can affect some properties of dielectric, especially electrical and thermal property.

Table 1 Compositions of  $\text{PbO-B}_2\text{O}_3\text{-SiO}_2\text{-Al}_2\text{O}_3$  glasses with variable ratios

Sample	Composition (wt%)				
	PbO	$\text{B}_2\text{O}_3$	$\text{SiO}_2$	$\text{Al}_2\text{O}_3$	$\text{RO}(\text{R}_2\text{O}_3, \text{RO}_2)/\text{Al}_2\text{O}_3$
S1	60	10	10	20	3 ( $\text{PbO}/\text{Al}_2\text{O}_3$ )
S2	65	10	10	15	4.3
S3	70	10	10	10	7
S4	75	10	10	5	15
S5	60	10	10	20	0.5 ( $\text{B}_2\text{O}_3/\text{Al}_2\text{O}_3$ )
S6	60	15	10	15	1
S7	60	20	10	10	2
S8	60	25	10	5	5
S9	60	10	5	25	0.2 ( $\text{SiO}_2/\text{Al}_2\text{O}_3$ )
S10	60	10	10	20	0.5
S11	60	10	15	15	1
S12	60	10	20	10	2

## Results and Discussion

The results of thermal expansion and dielectric constant on the PbO-SiO<sub>2</sub>-B<sub>2</sub>O<sub>3</sub>-Al<sub>2</sub>O<sub>3</sub> system are given in Figure 2-4. The relationship between the properties (dielectric constant and thermal expansion coefficient) and glass compositions were considered as a function of PbO/Al<sub>2</sub>O<sub>3</sub>, B<sub>2</sub>O<sub>3</sub>/Al<sub>2</sub>O<sub>3</sub> and SiO<sub>2</sub>/Al<sub>2</sub>O<sub>3</sub> ratios.

Figure 2 shows the dielectric constants considerably increase with increasing PbO/Al<sub>2</sub>O<sub>3</sub> ratio. PbO has highest dielectric constant (22.0 at 4.5 × 10<sup>8</sup> Hz) in comparison with B<sub>2</sub>O<sub>3</sub> (3.0), SiO<sub>2</sub> (3.8) and Al<sub>2</sub>O<sub>3</sub> (9.2), respectively. Although the thermal expansion coefficient of the glass is little sensitive to the change in the composition, it decreases gradually as the PbO/Al<sub>2</sub>O<sub>3</sub> ratio increases.

Figure 3-4 show the thermal expansion coefficients and the dielectric constants are slightly decreased with increasing B<sub>2</sub>O<sub>3</sub>/Al<sub>2</sub>O<sub>3</sub> and SiO<sub>2</sub>/Al<sub>2</sub>O<sub>3</sub> ratios. The original factors of each component to calculate thermal expansion coefficients from compositions are Al<sub>2</sub>O<sub>3</sub> (16.67 at 20/100°C), PbO (13), SiO<sub>2</sub> (2.67) and B<sub>2</sub>O<sub>3</sub> (0.33), respectively. As shown in the figures, the influence of Al<sub>2</sub>O<sub>3</sub> on the thermal expansion coefficient is small.

The dependence of thermal expansion coefficient on B<sub>2</sub>O<sub>3</sub>/Al<sub>2</sub>O<sub>3</sub> and SiO<sub>2</sub>/Al<sub>2</sub>O<sub>3</sub> ratio is consistent with the glass structure: the ionic radii of the ions Pb<sup>+2</sup>, Al<sup>+3</sup>, B<sup>+3</sup> and Si<sup>+4</sup> are 1.24, 0.51, 0.21 and 0.40 Å suggesting that as B<sup>+3</sup> has a greater strength of ionic field compared to Al<sup>+3</sup>. Hence the glass structure containing B<sub>2</sub>O<sub>3</sub> becomes stronger and is resulted in lower thermal expansion coefficient. The observed effects of SiO<sub>2</sub>/Al<sub>2</sub>O<sub>3</sub> on the dielectric constant of the glasses (S9-S12) agree with published data showing the similar trend [5]. The introduction of Al<sub>2</sub>O<sub>3</sub>, network modifier, raises the dielectric constant because of the formation of more easily polarizable non-bridging oxygen.

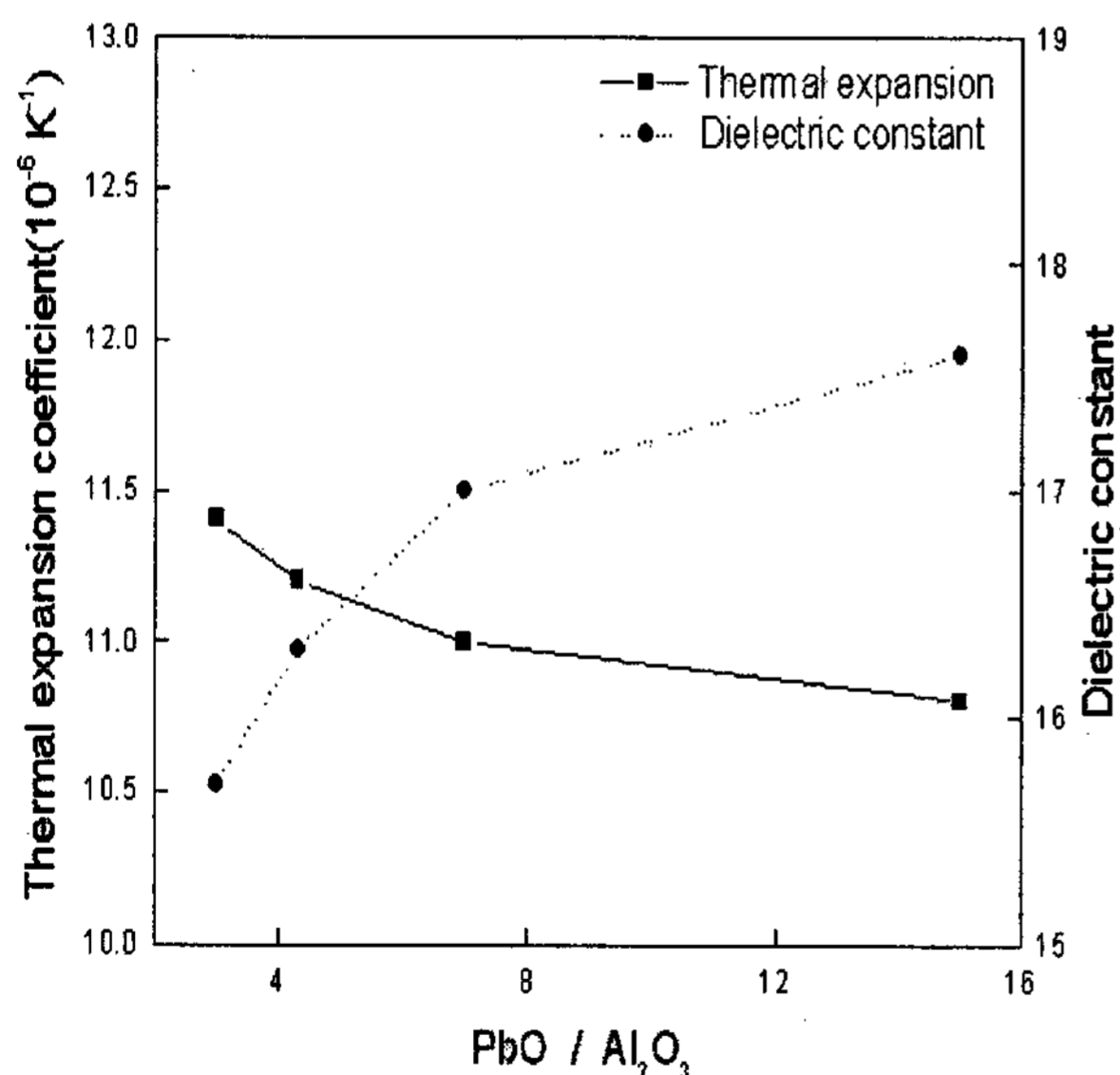


Fig. 2. Effects of PbO/Al<sub>2</sub>O<sub>3</sub> ratio on the thermal expansion coefficient and dielectric constant of PbO-SiO<sub>2</sub>-B<sub>2</sub>O<sub>3</sub>-Al<sub>2</sub>O<sub>3</sub> (S1-S4)

## Conclusion

We researched the effects of Al<sub>2</sub>O<sub>3</sub> in the PbO-SiO<sub>2</sub>-B<sub>2</sub>O<sub>3</sub> system by theoretical measurement. It was shown that thermal expansion and dielectric constant were greatly increased with increasing

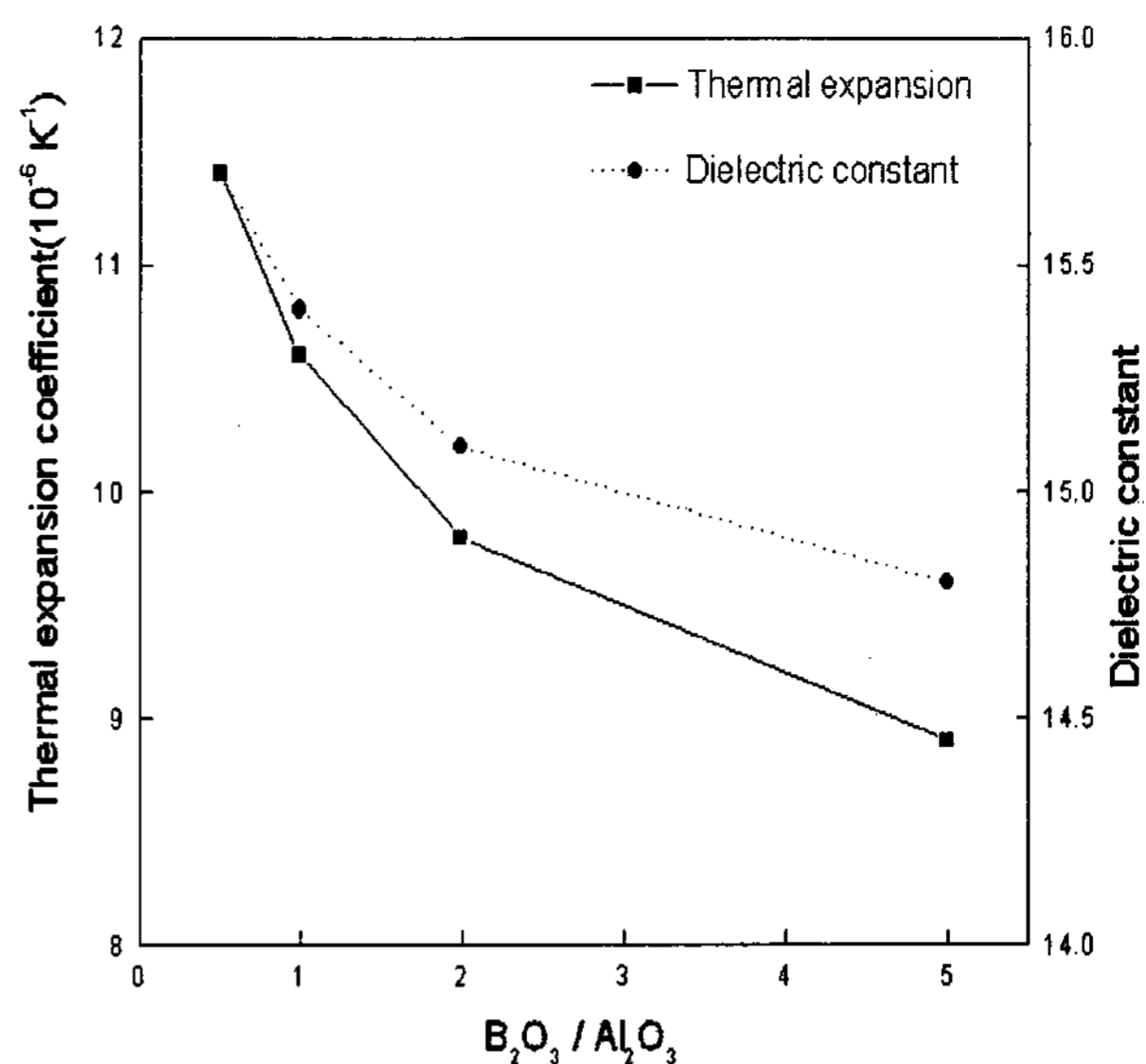


Fig. 3. Effects of B<sub>2</sub>O<sub>3</sub>/Al<sub>2</sub>O<sub>3</sub> ratio on the thermal expansion coefficient and dielectric constant of PbO-SiO<sub>2</sub>-B<sub>2</sub>O<sub>3</sub>-Al<sub>2</sub>O<sub>3</sub> (S5-S8)

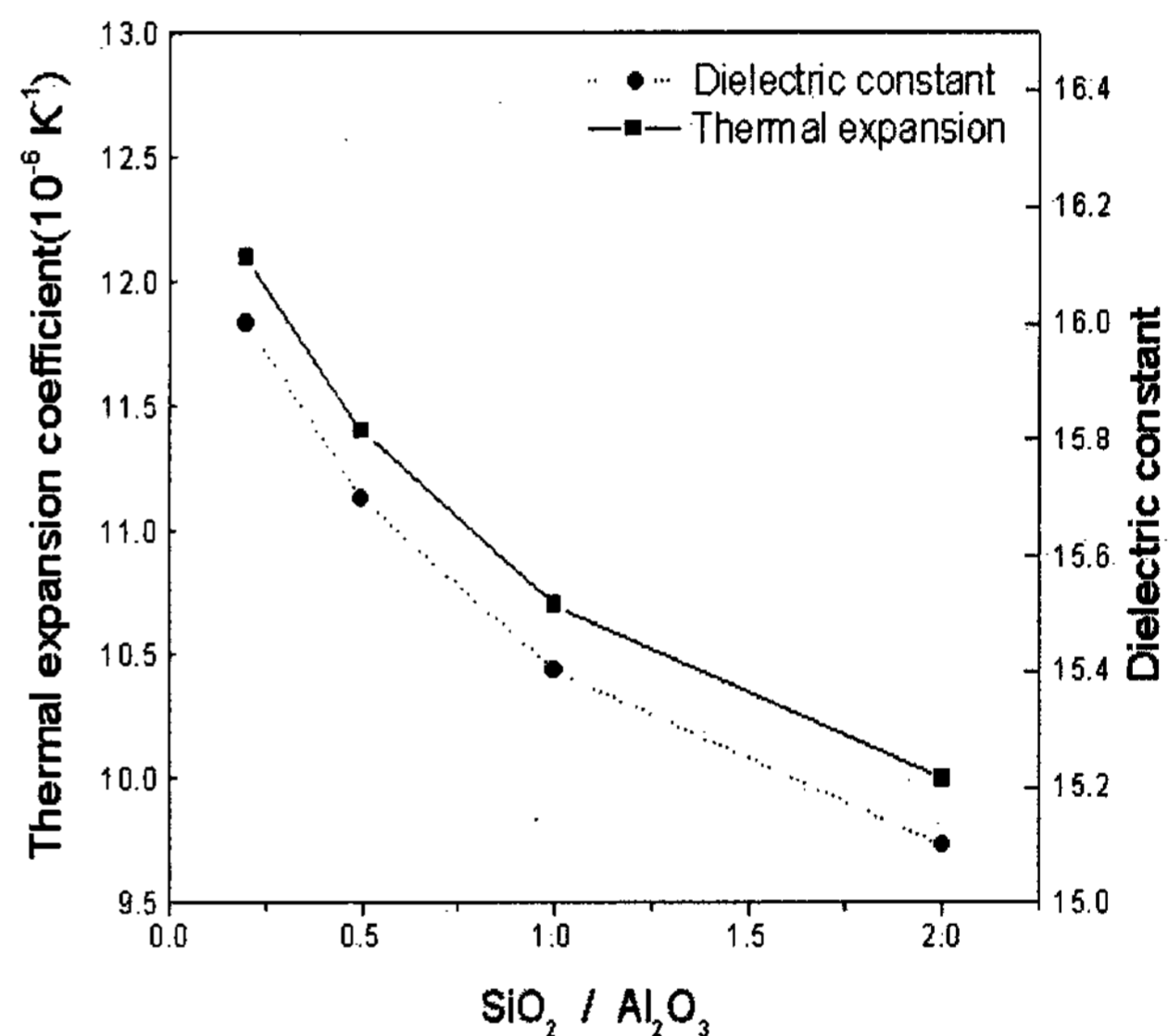


Fig. 4. Effects of SiO<sub>2</sub>/Al<sub>2</sub>O<sub>3</sub> ratio on the thermal expansion coefficient and dielectric constant of PbO-SiO<sub>2</sub>-B<sub>2</sub>O<sub>3</sub>-Al<sub>2</sub>O<sub>3</sub> (S9-S12)

PbO/Al<sub>2</sub>O<sub>3</sub> ratio, whereas B<sub>2</sub>O<sub>3</sub>/Al<sub>2</sub>O<sub>3</sub> and SiO<sub>2</sub>/Al<sub>2</sub>O<sub>3</sub> ratios were little sensitive to the properties.

## Reference

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